

# **Report on session 3A**

**« New EM developments »**

# 7 talks

**Firsov and Remizovich effects** *MANTERO, Alfonso et al.* 

for low energy low angle  
proton scattering simulation

**New evaluated PIXE model from** *GUATELLI, Susanna* 

ANSTO

*Aula Magna, Ferrara* 14:15 - 14:30

**New developments of MicroElec** *INGUIMBERT, Christophe*  
processes for low-energy electron  
transport in Al, Ag and Si

**Flagged uniform particle split** *RAMOS-MENDEZ, Jose* 

for Geant4-DNA *Aula Magna, Ferrara* 14:45 - 15:00

**MPEXS-DNA, a GPU implementation of** *OKADA, Shogo*  
Geant4-DNA

*Aula Magna, Ferrara* 15:00 - 15:15

**A Geant4 application for flexible and** *LAMPE, Nathanael*  
extendable DNA geometries  
incorporating physical and chemical genome damage

**Evaluation of radio-induced DNA** *MEYLAN, Sylvain*  
damages simulating the physical,  
physico-chemical and chemical stages with Geant4-DNA

# 1) A model for grazing angles soft proton scattering

A. Mantero, P. Dondero et al.

- @ 250 keV, Remizovich and SS consistent with exp data except below < 1 deg.
- SS is the closest to the observation for LowEn, BUT
  - Energy loss is 10 times lower
- MSC good for high energy, both for scattering and energy loss
- @ “large” incident angles all the models are consistent
  - the angular distribution does not depend on p energy
- Firsov ( $\varphi = 0$  Remizovich integration) overestimates 10 times exp data
- no differences are found between the EM opt3 and opt4 list multiple scattering settings.

More to do:

- Full Remizovich implementation
- Computing efficiency
- Geant4 integration

More work needed:

- Ad-Hoc measurements
  - Structures
  - Funding

## 2) The ANSTO Evaluated PIXE Model

CMRP: S. Guatelli and S. Bakr, ANSTO: D. Cohen and R. Siegele, Swhard:  
A. Mantero and P. Dondero, CENBG: S. Incerti

- New project
- Import in Geant4 the ANSTO Evaluated PIXE model
  - By J. Crawford, D. Cohen, R. Siegele, G. Doherty, A. Atanacio
  - Up to 5 MeV proton energy
  - Data available also for deuterium and helium as incident particles
  - Targets with Z between 6 and 92
  - Data provided within a self-consistent database, validated against experimental measurements
- Compare the alternative Geant4 PIXE models against experimental measurements of ANSTO micro-PIXE facility

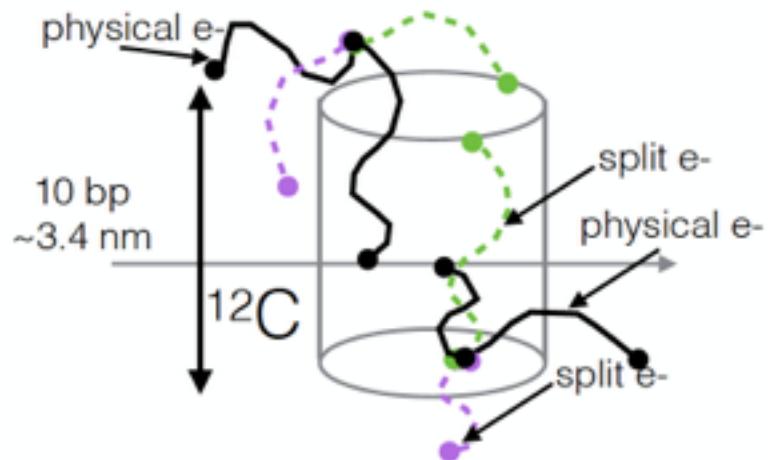
### 3) New developments for MicroElec (Al, Ag, Si)

C. Inguimbert, M. Raine

			Status	On going work
Date	2011	June 2012	September 2016	
Material	Al	Si	Si, Al implemented Cross section also calculated for Ag	Ag must be tabulated in MicroElec format
Energy range	10 eV – 5 keV	16,7 eV–100 MeV		
Inelastic model	Specific for each interaction in Al. ~4 eV	GLOBAL Dielectric function Formalism 16,7 eV	Inelastic cross section Down to ~1 eV in Si, Al	
Elastic model	Mott-ELSEPA <b>10 eV but all Z</b> [4]	ICRU [6] database <b>5eV for Si only</b>	Elastic cross section Down to 5 eV in Si and Al	Ag must be tabulated in MicroElec format
Geometry	No complex 3D	G4 3D	Available for all Z (NIST)	
Material interfaces	Vacuum/Al + surface plasmon	none		Vacuum/material interface not yet included
Phonons	Simplistic approach	none	Some comparisons with experimental electron secondary emission yield have been performed	Phonons not yet implemented
Observables	Secondary Electron Emission -SEE Yield -Energetic spectrum -Angular distribution	User defined Track structure of heavy ions		

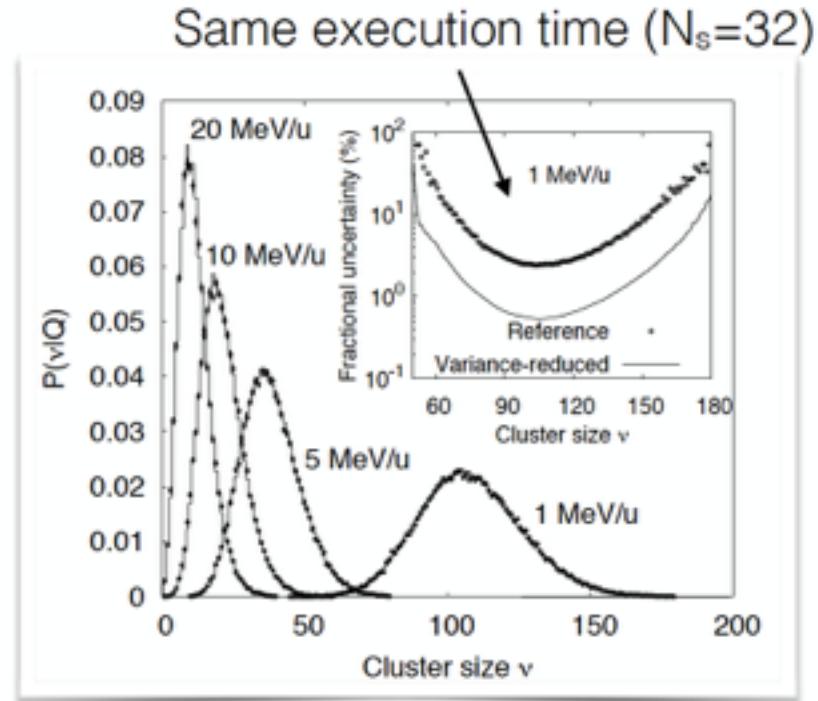
## 4) Flagged uniform particle split for Geant4-DNA

J. Ramos-Mendez, B. Faddegon



- This study showed that the flagged uniform particle split allows to achieve significant improvement of the computational efficiency of Geant4-DNA simulations without compromising the accuracy.
- For protons, the relative efficiency ranged from **50 to 350** (less complex scoring, high to low LET). For carbon ions, the relative efficiency ranged from about **45 to 55** (simple scoring, high to low LET). In both scenarios, the relative differences between variance-reduced and reference simulations were within the 2% within the statistical uncertainty.

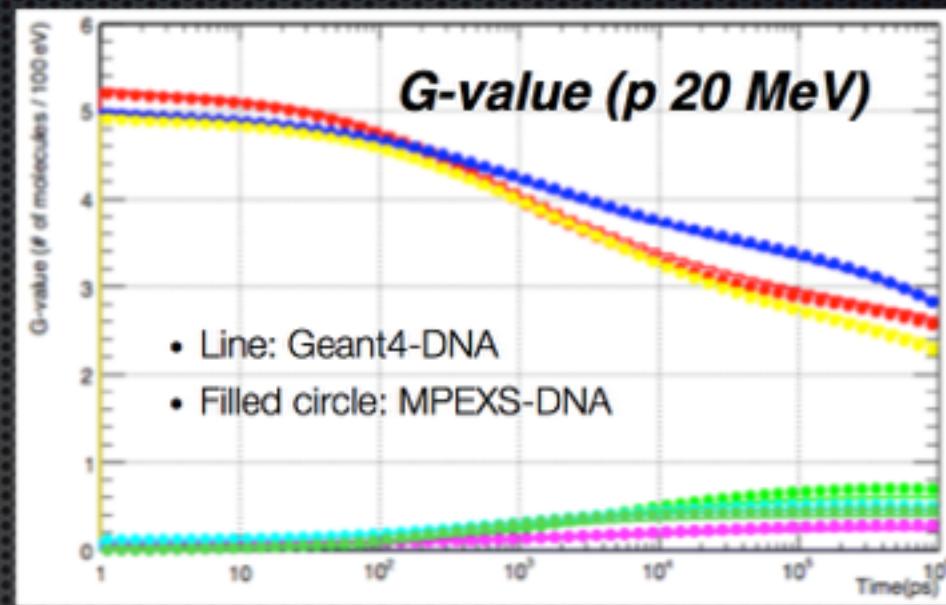
- Uniform splitting is applied to e-\_G4DNAIonisation via G4WrapperProcess
- A unique flag (integer number) is assigned to each new split particle.
- This flag must be **inherited** to all subsequent secondaries.
- Use this flag to classify all the tracks independently



## 5) MPEXS-DNA, a GPU implementation of Geant4-DNA Summary

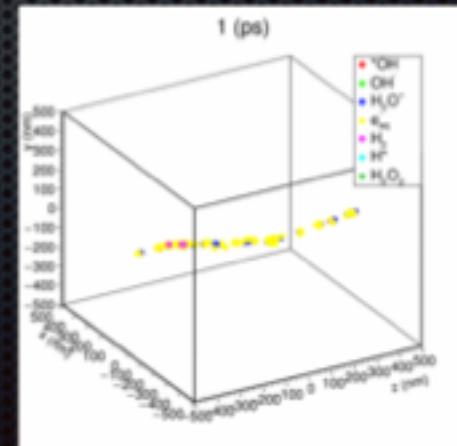
S. Okada et al.

- DNA Physics and Chemical simulation can be run on GPU
  - Geant4-DNA processes are implemented in CUDA
  - MPEXS-DNA have the same accuracy as Geant4-DNA



- **Achieve up to 200 times speedup agains single-core CPU**
- ~ 2.5 days (CPU) -> **~ 20 min. (GPU)** (ex.  $p$  20 MeV, 10k events)

	e- 10 keV	e- 750 keV	p 20 MeV
Water phantom size	1 x 1 x 1 um	5 x 5 x 5 um	1 x 1 x 1 um
Average # of molecules generated at 1 ps	419	126	347
Process time (Geant4-DNA 10.02 p01)	30.6 sec / event	5.01 sec / event	22.1 sec / event
Process time (MPEXS-DNA)	0.197 sec / event	0.0336 sec / event	0.115 sec / event
Speedup factor	<b>155x</b>	<b>149x</b>	<b>192x</b>

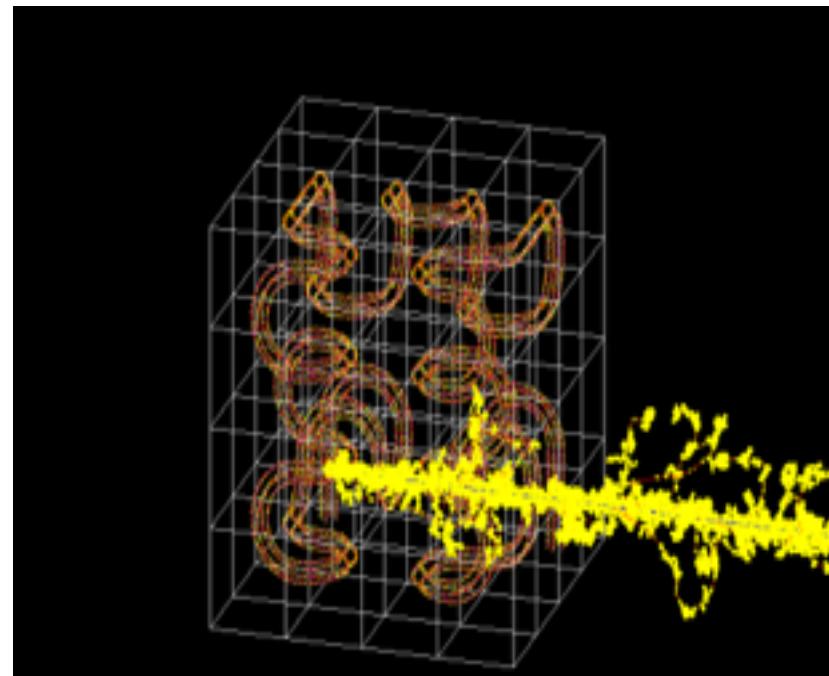


# 6) The MolecularDNA Application

N. Lampe

- A monolithic application simulating direct and indirect DNA damage
- Flexible specification of DNA geometries
  - Ships with bacterial DNA
  - Extendable to chromatin, plasmids, test DNA geometries, all without touching C++
- Coming early 2017

1 MeV protons travelling through a simple continuous DNA model



## 7) Evaluation of radio-induced DNA damages simulating the physical, physico-chemical and chemical stages with Geant4-DNA

S. Meylan

- DnaFabric 
  - ✓ Generate/Edit/Save complex DNA geometries
  - ✓ Visualize
  - ✓ Export to Geant4-DNA (“.fab2g4dna” file)
- Simulate the physical, physico-chemical and chemical stages with such geometrical models.
- Results are consistent with experimental data
- Criteria associated with the creation of DNA damages are not “set in stone”:
  - Direct SSB threshold or linear acceptation probability
  - Duration of the chemical stage (by default 2.5 ns).

What will be delivered:

- ✓ A user-application to show how to introduce a DNA geometrical model in a chemical simulation.
- ✓ To do so, some of the Geant4 modifications should be integrated.